35.C10530C/D2

PATENT APPLICATION

10127199 A.Jenkins

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: KIYOFUMI SAKAGUCHI, ET AL. Application No.: 09/161,774 Filed: September 29, 1998) :) :)	Examiner: Group Art		•		S
For: PROCESS FOR PRODUCTION OF SEMICONDUCTOR SUBSTRATE	;) ;	September	22, 1	TC 28	:0	23
Assistant Commissioner for Pat Washington, D.C. 20231	ents			2600 HAIL	e:::23 ls	CEIVE
SECOND PRELIM	<u> [NARY</u>	AMENDMENT		ROOM	133	

Sir:

Prior to examination on the merits, please further amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel Claims 22 - 96 without prejudice to or disclaimer of the subject matter recited therein.

Please add new Claims 97 through 104 as follows:

97. A method for separating a semiconductor layer from a substrate, comprising:

forming a porous layer on a surface of a substrate by an anodic oxidization;